

AMENDMENTS TO THE SPECIFICATION

Please replace paragraphs 0018, 0027 and 0074¹ of the specification with the following replacement paragraphs:

[0018] The invention enables large surfaces, visible to the naked eye, to be covered with a uniform grating, namely in a simple, non-holographic fashion, [[e.g.]] for example, by means of a focussed radiation, in particular an electron beam. [[I.e.]] That is, a motif to be depicted is divided into individual image fields, which have an extent visually perceptible and these image fields are covered with a uniform grating. In this way the light intensity of the grating image can be increased, since unexposed spacings do not exist. The distortion of colours is also prevented, because the fields are covered over a large area with a grating and are not composed of small-surfaced dots with interfering spacings.

[0027] The invention, however, is not restricted to the use of ruled gratings as grating pattern. Instead of straight grating lines also curved, wave-shaped or any other not straight grating patterns can be used. In this case it is not sufficient to store only the coordinates of the intersection points, the grating lines forming the grating pattern have with the contour line, as starting points and end points. Furthermore, information about the path of the grating lines within the contour line has to be provided. For that purpose the coordinates of any number of intermediate points can be used, which as a polygonal curve describe the form of the grating line.
[[line]] Alternatively, the form of the grating line can also be described as a Bezier curve, in

¹ In conformance with the Office Action, all cites to Applicant's specification refer to U.S. Pat. App. Pub. No. 2006/0152807.

which the coordinates of merely a few intermediate points and additionally a tangential direction with respect to the further path of the curve are stored.

[0074] It is pointed out, that the Figures are of a mere schematic nature and only serve for illustrating. In practice the contour lines or the extent of the grating fields lie within the millimeter and centimeter range. The spacings between the grating lines lie in the micrometer range and ~~therebelow. I.e.,~~ therebelow, that is, when in the Figures only few grating lines are drawn, in practice this corresponds to up to several thousands of grating lines. The electron beam as a lithography instrument permits very fine resolutions, which reach the nanometer range. For this reason it is preferably used. In case gratings are to be written, which do not require such a high resolution, also other lithography instruments are possible as to form the grating lines 13 in a substrate. Possible methods are mechanical engraving with a precision milling apparatus or another form of material removal, e.g. with a focussed UV laser. In principle all instruments can be used, which permit a writing of lines, on the basis of the above-mentioned data records, each starting at a starting point and ending at an end point, in a sufficiently fine line thickness onto a suitable substrate. Such a series of material processing leaves characteristic marks in the substrate, due to which the person skilled in the art at least with the help of an electron microscope can recognize, which type of instrument was used for producing the lines in the substrate.